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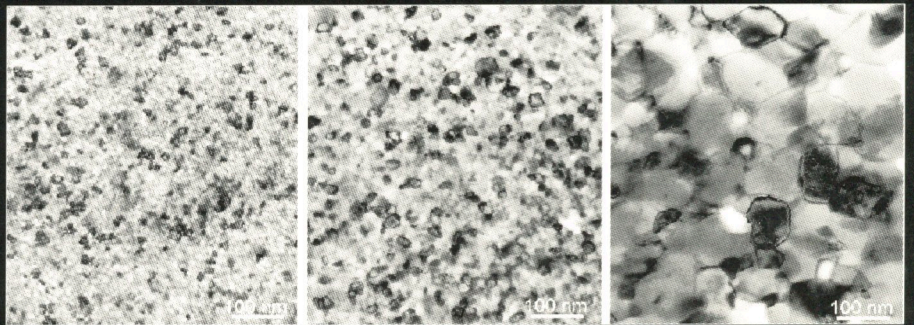
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# Applied Physics

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Special issue on the future of technological plasmas

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